

	$\gamma\text{-Al}_2\text{O}_3$, °	h ,	$\alpha\text{-Al}_2\text{O}_3$ 100 , %
99	7,895	30	75
6	7,920	50	50
16	7,925	60	40
95	7,932	90	10

, $\gamma\text{-Al}_2\text{O}_3$
 $\gamma \rightarrow \alpha$,
 $\alpha\text{-Al}_2\text{O}_3$.

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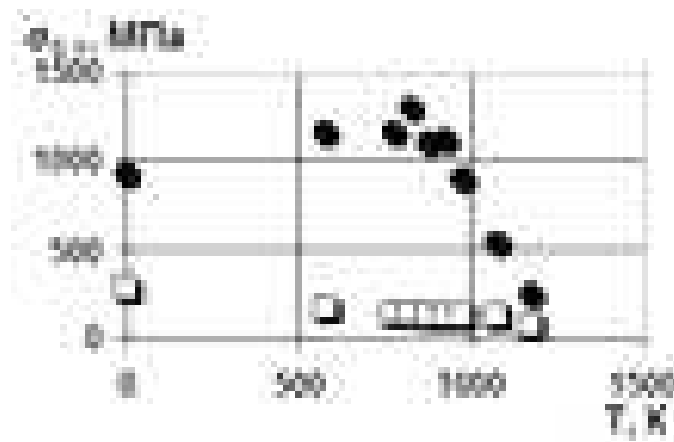
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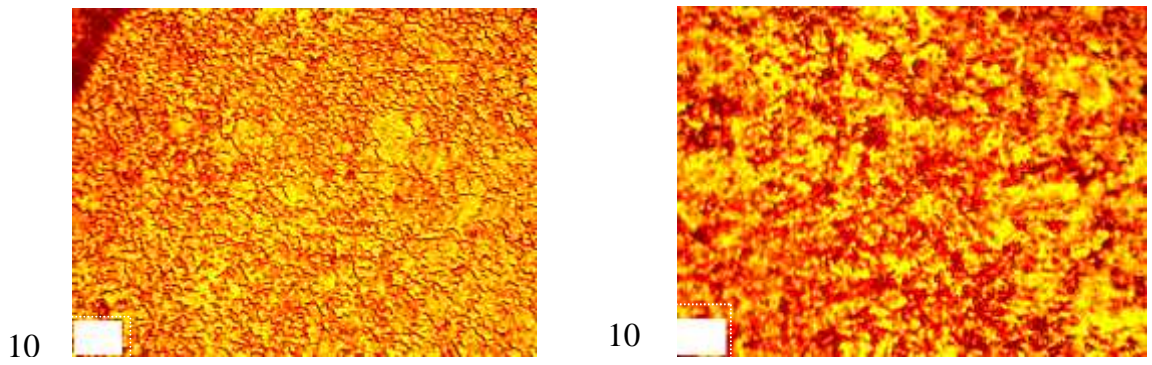
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